



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:  
HONGO *et al.*

Confirmation No. 4649

RECEIVED  
APR 09 2003  
GROUP 1700

Application No.: 09/815,305

Filed: March 23, 2001

ART UNIT: 1763

Title: PLASMA PROCESSING APPARATUS  
HAVING AN EVACUATING ARRANGEMENT TO  
EVACUATE GAS FROM A GAS-INTRODUCING  
PART OF A PROCESS CHAMBER

Examiner: ALEJANDRO MULERO, L.

\* \* \* \*

#11B  
4/10/03  
mcs  
April 8, 2003

AMENDMENT

Hon. Commissioner of Patents  
Washington, DC 20231

Sir:

Responsive to the Office Action dated January 09, 2003, please amend the above identified application as follows:

IN THE CLAIMS

Please amend claim 16 as follows:

16. (Amended) The plasma processing apparatus as claimed in claim 15, wherein said gas-introducing part comprises:

at least one inlet port from which the reactant gas is supplied;

B, an annular gas passage connected to said inlet port so that the reactant gas supplied from the inlet port is supplied to said plurality of nozzles by flowing through said annular gas passage; and

an outlet port provided to said annular gas passage so that said gas-evacuating arrangement is connected thereto.

*See the attached Appendix for the changes made to effect the above claim(s).*